LASER-INDUCED TRANSFORMATIONS IN THERMALLY EVAPORATED THIN TlInSe$_2$ FILMS STUDIED BY RAMAN SPECTROSCOPY

TlInSe$_2$ films with thickness from 10 to 200 nm were thermally evaporated on silicon and silicate glass substrates. Micro-Raman spectra measured at a moderate excitation (532 nm, 4 kW/cm$^2$) confirm the amorphous character of the films. Narrow features revealed in the spectra at an excitation power density of 40 kW/cm$^2$ show the evidence for the formation of TlInSe$_2$, TlSe, and In$_2$Se$_3$ crystallites in the laser spot. For thin (10–30 nm) films, the rod-shaped TlInSe$_2$ crystallites are shown to be oriented within the film plane. The crystallite formation is governed by the thermal effect of the tightly focused laser beam.

Key words: thin films, thermal evaporation, Raman spectroscopy, crystallisation.

1. Introduction

TlInSe$_2$ is a rather well-known semiconductor material with chain-like structure (tetragonal crystal system) [1]. It is extensively studied [2–9], in particular, in view of possible phase transitions (which are still questionable) [10, 11, & references therein]. It is sometimes referred to as a quasi-one-dimensional or one-dimensional (1-D) material [4], and several publications were devoted to the properties of nanoscale (30–50 nm) TlInSe$_2$ structures [3, 12]. Properties of TlInSe$_2$ make it promising for applications in acousto-optics [11], electronics [13], thermoelectricity [3, 9], neutron and γ-ray detection [7]. Important information about the crystal structure and lattice dynamics of TlInSe$_2$ can be gained from Raman spectroscopy [2, 5, 8, 14, 15].

In the recent years, an additional research interest toward thin TlInSe$_2$ films emerged [16, 17], similarly to the films of related I–III–VI$_2$ materials prepared mostly by the thermal evaporation [18–26].

Here, we present a Raman spectroscopic study of structural transformations in thermally evaporated thin TlInSe$_2$ films under the illumination by a tightly focused laser beam.

2. Experimental

TlInSe$_2$ films with thickness $d$ from 10 to 200 nm were prepared by the thermal evaporation of pre-synthesised crystalline TlInSe$_2$ (the synthesis details can be found elsewhere [14]) on silicon and silicate
glass substrates at room temperature at a pressure of \( \sim 2 \times 10^{-4} \) Pa with an evaporation rate of 4 nm/s. The evaporation temperature was 1050 K. The thickness of the films was roughly estimated by interferometry (for the thicker films) and by interpolation with the account for the evaporation time (for the thinner samples).

Micro-Raman scattering measurements were carried out at room temperature using an XPloRa Plus spectrometer (Horiba). Excitation was provided by a solid-state laser \((\lambda_{\text{exc}} = 532 \text{ nm})\). The scattered light was detected by a cooled CCD camera. The instrumental resolution was better than 2.5 cm\(^{-1}\).

3. Results and Discussion

Raman spectra of TlInSe\(_2\) films on silicate glass and silicon substrates measured at a low excitation power density \((P_{\text{exc}} = 4 \text{ kW/cm}^2)\) are shown in Fig. 1. The features in the spectra are noticeably broader than for single-crystal TlInSe\(_2\) \([8, 14]\). Hence, the films can be treated as amorphous. The half-width of the most intense maximum near 165 cm\(^{-1}\) is in the interval 20–35 cm\(^{-1}\) for the films evaporated on the glass substrate and 15–35 cm\(^{-1}\) for the films on the silicon substrate. While for the samples on the glass substrate there is no clear dependence of the band half-width on the film thickness, for those on the silicon substrate a trend of the peak narrowing with the film thickness is observed.

In our opinion, an even clearer evidence of the amorphous structure of the films is the frequency position of the most intense peak (near 165 cm\(^{-1}\)) which, for TlInSe\(_2\), should be expected near 180–185 cm\(^{-1}\). Note that a recent study performed for thermally evaporated polycrystalline TlInSe\(_2\) films clearly revealed the dominant Raman peak at 181 cm\(^{-1}\) and a less intense feature at 169 cm\(^{-1}\) \([17]\). Likewise, the spectrum of single-crystal TlInSe\(_2\) in \(Z(XX + XY)Z\) scattering configuration exhibits the most prominent narrow peak at 185 cm\(^{-1}\), a less intense maximum at 171 cm\(^{-1}\), and an even weaker shoulder near 200 cm\(^{-1}\) (Fig. 2). Similar spectra were observed for single-crystalline TlInSe\(_2\) in earlier studies \([8, 14]\). The most intense feature corresponds to fully symmetric vibrations of \(A_{1g}\) symmetry, while the features at 173 m\(^{-1}\) and 205 cm\(^{-1}\) (see the inset in Fig. 2) are attributed to vibrations of \(E_g\) and \(E_u\) symmetry, respectively \([8]\).

![Fig. 1.](image1)  
Micro-Raman spectra of TlInSe\(_2\) films of different thicknesses \(d\), thermally evaporated on silicate glass (\(a\)) and silicon (\(b\)) substrates. The spectra were measured at the excitation with \(\lambda_{\text{exc}} = 532 \text{ nm}\) and \(P_{\text{exc}} = 4 \text{ kW/cm}^2\).

![Fig. 2.](image2)  
Micro-Raman spectrum of a single-crystal TlInSe\(_2\) sample in \(Z(XX + XY)Z\) scattering geometry measured at the excitation with \(\lambda_{\text{exc}} = 532 \text{ nm}\) and \(P_{\text{exc}} = 40 \text{ kW/cm}^2\). The inset shows the simulation of the observed Raman spectrum by three Lorentzian contours, the frequency positions and half-widths (in parentheses) being indicated.

In the case of TlInSe\(_2\) films (Fig. 1), the absence of peaks close to the mentioned frequencies means the absence of clearly defined TlInSe\(_2\) structural groups in the film (i.e., their amorphous character), while...
The most intense peak near 165 cm$^{-1}$ corresponds to the vibrations of Tl–Se bonds in the amorphous film structure. Such feature is known to be observed in the Raman spectra of TlSe crystals [27] and thin films [28]. Meanwhile, In–Se bonds in the spectra of the amorphous films contribute to a broad continuum-like structure in the interval 200–250 cm$^{-1}$ (Fig. 1). An intense broad band in this spectral interval is reported for amorphous In$_2$Se$_3$ films [29].

Evidently, the reason for why, in our case, contrary to the recent studies of other groups [16, 17], the thermal evaporation resulted in amorphous TlInSe$_2$ films, is related to the substrate temperature. The authors of Refs. [16, 17] evaporated the films on substrates heated to 300–350 $^\circ$C and obtained polycrystalline TlInSe$_2$ films, their structure being clearly confirmed by the X-ray diffraction and Raman spectroscopy. Meanwhile, in our case, the evaporation was performed onto cold substrates, and amorphous TlInSe$_2$ films were obtained.

Raman measurements performed for the same TlInSe$_2$ film samples at an increased $P_{\text{exc}} = 40$ kW/cm$^2$ (Fig. 3) revealed intense narrow maxima which clearly indicates a fast crystallization of the film material in the laser spot. Contrary to the low-$P_{\text{exc}}$ spectra which look much similar for the samples prepared at different substrates and with different film thicknesses (Fig. 1), the spectra measured at $P_{\text{exc}} = 40$ kW/cm$^2$ exhibit different peaks depending on the film thickness and the substrate type. The dependences are not always clearly defined, but some general trends can be pointed out.

Unpolarized room-temperature Raman spectra of crystalline TlInSe$_2$ in this frequency interval [8, 14], similarly to the spectrum shown in Fig. 2, demonstrate the most intense $A_{1g}$ symmetry peak at 183–186 cm$^{-1}$ and another one of $E_g$ symmetry at 171–173 cm$^{-1}$ which is weaker by about an order of magnitude [8, 14]. In the films under investigation, the peak at 181–184 cm$^{-1}$ is observed for films of all thicknesses on the silicon substrates and for the thickest (200 nm) film on the silicate glass substrate. Meanwhile, the $E_g$ band at 171–175 cm$^{-1}$ is revealed only for thinner films (10–30 nm): for the films on the silicate glass substrate, it is the predominant peak in the spectra; while for the samples on the silicon substrate, it is only slightly weaker than the strongest peak at 181–184 cm$^{-1}$ (Fig. 3). Such behavior means that, for these films, the TlInSe$_2$ crystallites formed in the laser spot are not randomly oriented, because otherwise the ratio of the intensities of two bands in the spectrum would be close to that in the unpolarized spectrum of crystalline TlInSe$_2$. Note that, due to the chain-like structure of TlInSe$_2$, its nanocrystallites are known to be of elongated, rod-like shape [3, 12]. According to the group-theoretic analysis [2], the vibration of $E_g$ symmetry (171–175 cm$^{-1}$) corresponds to the $(XZ)$ and $(YZ)$ components of the Raman tensor. Taking into account the backscattering configuration, the observed preferential contribution from these components means that the TlInSe$_2$ nanorods should be oriented with the $Z$ direction (the nanorod axis) mostly within the film plane. Evidently, the restriction of the in-plane orientation of the nanorods was imposed by the small (10–30 nm) film thickness, since for thicker films the intensity of the $E_g$ band at 171–175 cm$^{-1}$ is negligible (Fig. 3) meaning that, in this case, the TlInSe$_2$ crystallites formed in the laser spot are randomly oriented.

However, besides the discussed TlInSe$_2$ peaks, there are more narrow features formed in the TlInSe$_2$ films and revealed in the spectra under the illuminating laser light.
nation with $P_{\text{exc}} = 40 \text{ kW/cm}^2$. The most intense are the peaks at 155–160 cm$^{-1}$ and 108 cm$^{-1}$ (the latter is observed only for the films of smaller thicknesses). The peak near 160 cm$^{-1}$ is known to be the most prominent Raman feature of crystalline TlSe [27], while the one at 104 cm$^{-1}$ was reported as the most intense feature of $\alpha$-In$_2$Se$_3$ crystal [30]. It can be concluded that the high-$P_{\text{exc}}$ illumination leads to the formation of not only TlInSe$_2$, but also TlSe and In$_2$Se$_3$ crystallites in the illuminated area of the amorphous TlInSe$_2$ films.

The earlier formation of TlInSe$_2$ crystallites under the intense laser illumination was reported for Tl–In–As–Se glass [31] similarly to the formation of other chalcogenide nanocrystals in amorphous As$_2$Se$_3$-based films [32,33]. In all cases, Raman spectroscopy was used to confirm the crystallite formation. It is essential that, in all those cases, the mechanism of this photoinduced effect is mostly nonthermal, based on a drastic drop of the material viscosity caused by the local photofluidization due to the interaction of the tightly focused laser beam with the amorphous As$_2$Se$_3$-based material. Note that, for those materials, the accompanying photoinduced effect of mass transport from a heavily illuminated area was revealed as the formation of a pit in the laser spot on the film surface [31–33]. In our case, on the contrary, we did not observe any damage on the film surface after the illumination and the Raman measurement. From this, we conclude that the formation of crystallites in the films in the course of the Raman measurement at the elevated $P_{\text{exc}}$ is driven by a thermal mechanism: the sample surface in the laser spot is heated by the tightly focused laser beam and thermally enhanced mobility enables the localized crystallite formation.

In order to check whether the structural changes in the TlInSe$_2$ films leading to the observed crystalline features emerging in their Raman spectra at a higher power density are indeed related to the thermal effect of the tightly focused laser beam, we performed the 30-min annealing of the TlInSe$_2$ film samples at 150 °C and 300 °C and subsequent measurements of their Raman spectra. The Raman measurements were performed at low $P_{\text{exc}} = 4 \text{ kW/cm}^2$ to avoid an additional sample heating. The corresponding Raman spectra shown in Fig. 4 clearly reveal the intense sharp peaks emerging at 153–155 cm$^{-1}$ and 181–185 cm$^{-1}$, as well as a less pronounced feature at 173 cm$^{-1}$. In view of the above discussion, it is quite reasonable to relate the peak at 153–155 cm$^{-1}$ to the TlSe crystallites and the features at 173 cm$^{-1}$ and 181–185 cm$^{-1}$ to the TlInSe$_2$ crystallites which evidently appear in the sample after the annealing. The spectra of the thermally annealed samples strongly resemble those of the untreated TlInSe$_2$ films measured at the higher $P_{\text{exc}} = 40 \text{ kW/cm}^2$ (Fig. 3). These data clearly confirm that the crystallization effects revealed for the TlInSe$_2$ films under the higher $P_{\text{exc}}$ illumination result from the thermal effect of the focused laser beam.

4. Conclusions

TlInSe$_2$ films with thickness from 10 to 200 nm are prepared by the thermal evaporation on silicon and silicate glass substrates. Micro-Raman spectra measured at $\lambda_{\text{exc}} = 532 \text{ nm}$ and the moderate excitation power density $P_{\text{exc}} = 4 \text{ kW/cm}^2$ show the dominating contribution from Tl–Se bond vibrations and confirm the amorphous character of the films.

At the elevated power density 40 kW/cm$^2$, narrow features emerge in the spectra, showing the evidence for the formation of TlInSe$_2$ as well as
TISe and In$_2$Se$_3$ crystallites in the laser spot on the film surface. Based on the peak intensities, it is shown that, for thin (10–30 nm) films, the rod-shaped TlInSe$_2$ crystallites are oriented within the film plane. The formation of the crystallites is explained by the thermal effect of the tightly focused laser beam facilitating the mobility of atoms in the illuminated area. This conclusion is confirmed by the Raman measurements performed for the TlInSe$_2$ films annealed for 30 min at 150 and 300 °C which show the appearance of remarkably similar crystallite-related peaks.

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РАМАНІВСЬКЕ ДОСЛІДЖЕННЯ ІНДУКОВАНИХ ЛАЗЕРНИМ ВИПРОМІНЮВАННЯМ ПЕРЕТОВАРЕЛЬ У ТЕРМІЧНО НАПИЛЕНИХ ТОНКИХ ПЛІВКАХ TIlnSe$_2$

Плівки TIlnSe$_2$ товщиною від 10 до 200 нм отримано термічним напіленням на підкладки з кремнію та силикатного скла, що перебували при кімнатній температурі. Мікрораманівські спектри, виміряні при помірній густині потужності (532 нм, 4 кВт/см$^2$), підтверджують аморфний характер отриманих плівок. При підвищенні густини потужності до 40 кВт/см$^2$ у спектрах з’являються вузькі лінії, спектральне положення яких вказує на формування кристалітів TIlnSe$_2$, а також TlSe та In$_2$Se$_3$ у місці падіння лазерного променя на поверхню плівки. Показано, що для тонких (10–30 нм) плівок кристаліти TIlnSe$_2$ мають видовжену форму і орієнтовані в площині плівки. Термічна кристалізація обумовлена локальним нагріванням плівки сильнопронизованим лазерним пучком.

Ключові слова: тонкі плівки, термічне напілення, рamanівська спектроскопія, кристалізація.